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## Phosphorus, Sulfur, and Silicon and the Related Elements

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*Phosphorus, Sulfur, and Silicon and the Related Elements* welcomes submissions involving the chemistry, inorganic, and biochemistry of phosphorus (including arsenic, antimony, and bismuth), sulfur (including selenium and tellurium), and silicon (including germanium and tin). In addition to research describing new chemistry of a particular element, especially welcome are presentations emphasizing relationships between elements and families of elements; for example, research comparing synthetic, mechanistic, or structural features providing new insight leading to a more rapid advance of science in these areas.

Original articles, communications, and selected reviews of broad interest will be considered for publication. Manuscripts may include illustrative material in color if this will enhance the presentation. There are no page charges and 25 free reprints will be supplied to the principal author. Regular papers may be sent to R. R. Holmes in Amherst or to L. Maier in Basel. Communications and reviews should be sent to W. Walter in Hamburg or J. G. Verkade in Ames. Notes for contributors, including information on communications and reviews, can be found at the back of every issue.

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